	18th of November
08:30-08:35	Opening
08:35-09:20	**Prof. Timon Fliervoet** *Technical University Delft and ASML-Research Veldhoven, The Netherlands* Low-Energy Electrons: From Nanometer-Scale EUV Patterning to Metrology and Inspection
09:20-09:40	**Dr. Joannis Koepsell** *Carl Zeiss SMT GmbH, Rossdorf, Germany* Semiconductor mask repair with focused electron-beam induced processing
09:40-10:10	CoMee
	10:10-15:00 Conference excursion
15:30-16:00	**Dr. Jakub Mateusz Jurczyk** *Technical University Vienna, Vienna, Austria* 3D nanoprinting with electrons: shape, composition and in-situ process analysis
16:00-16:20	**Ms. Alix Tatiana Escalante-Quiceno** *INMA (CSIC – Universidad de Zaragoza), Spain* Focused Electron and Ion Beam Processing for High-Resolution AFM and MFM Probes
16:20-16:50	Coffee
16:50-17:10	**Dr. Ivo Utke** *Swiss Federal Laboratories for Materials Science and Technology (EMPA), Thun, Switzerland* The fate of metalorganic molecule ligands in e-nanoprinting
17:10-17:30	**Dr. Katja Höflich** *Ferdinand-Braun-Institut (FBH), Berlin, Germany* Electron beam seeding as a new tool for area-selective deposition of gold
17:30-17:50	**Prof. Armin Gölzhäuser** *Bielefeld University, Bielefeld, Germany* Carbon Nanomembranes: Radiation-induced 2D Materials for Separation
	Posters are on display throughout the conference
18:30-22:00	**Conference dinner**